

# Resin Wafer-Electrodeionization for Flue Gas Carbon Dioxide Capture

DOE Program Announcement Number: DE-FOA-0000065

ARPA-E Award: DE-AR0000024

2010 NETL CO<sub>2</sub> Capture Technology R&D Meeting  
Pittsburgh, PA  
September 14, 2010



Lead Recipient:	Nalco Company
Project Title:	Energy Efficient Capture of CO <sub>2</sub> from Coal Flue Gas
Nalco Principal Investigator:	Jitendra T. Shah
Argonne Principal Investigator:	Yupo J. Lin

Presented by Jitendra T. Shah and Wayne M. Carlson

# A new strategy for CO<sub>2</sub> capture: CO<sub>2</sub>\_RW-EDI

## Strategy:

- Addresses CO<sub>2</sub> absorption & release
  - Resin Wafer-Electrodeionization designed and developed to capture and release CO<sub>2</sub> (CO<sub>2</sub>\_RW-EDI)
  - Kinetics enhanced with carbonic anhydrase enzyme
- Employs electrochemical pH control
  - pH shifts capture and release CO<sub>2</sub> in separate cells
  - Water splitting enables in-situ pH control for optimum activity
  - Eliminates the need for acids and bases
- Decreases parasitic energy load
  - Avoids temperature and/or pressure swings for regeneration
  - Avoids the use of steam and vacuum

# Project goals will significantly advance CO<sub>2</sub> capture technology

## Project Goals

- Develop Resin Wafer-Electrodeionization technology for CO<sub>2</sub> capture
- Target 90% CO<sub>2</sub> capture and released CO<sub>2</sub> with 90% purity
- Establish a prototype demonstration of a pilot system that captures CO<sub>2</sub> at an effective rate of 1 tonne/day, Technology Readiness Level 6 (TRL-6)

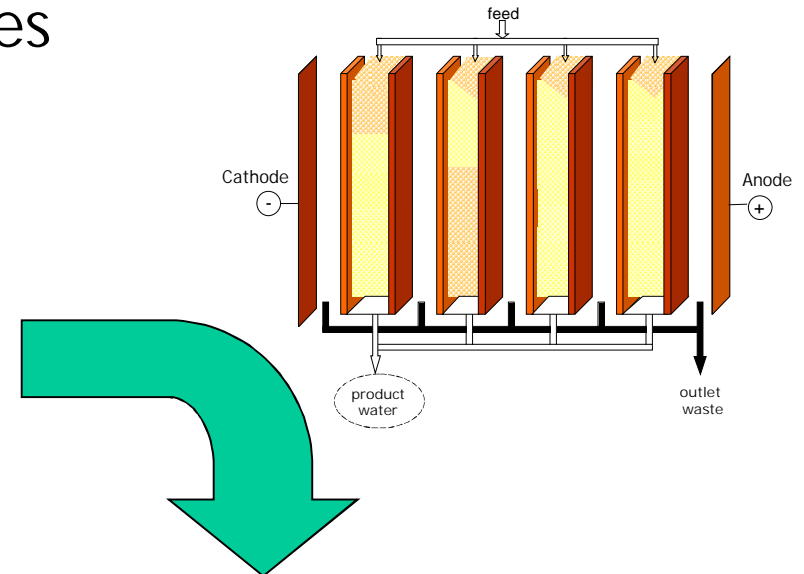
## Project benefits for the environment & consumers

- Energy-efficient CO<sub>2</sub> capture to mitigate climate change
- Minimize the impact on cost of electricity (by as much as 50% to keep coal-fired power production affordable)
- Easily retrofitted to existing industrial facilities and compatible with carbon storage technologies
- Make clean CO<sub>2</sub> available for beneficial uses such as algal biofuels, renewable plastics, etc.
- Develop advanced manufacturing capabilities in the U.S.

# What is RW-EDI?

RW-EDI is based on a progression of water purification technologies

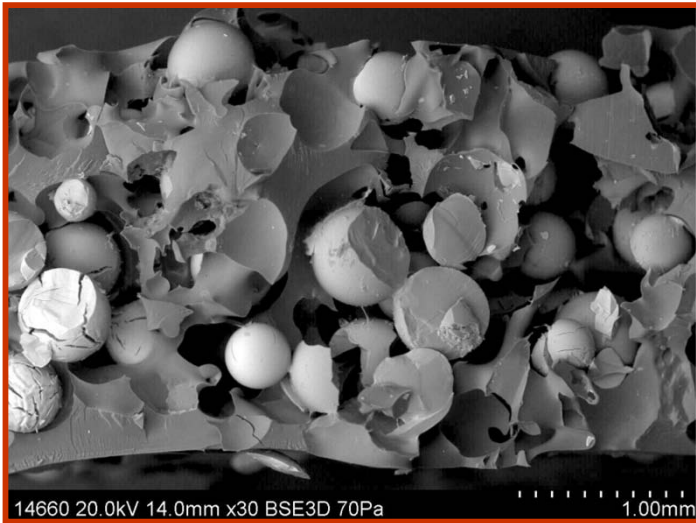
- Ion Exchange (IX)
- Electrodialysis (ED)
- Electrodeionization (EDI)



## Resin-Wafer Electrodeionization (RW-EDI)

- Liquid Systems
- Gas/Liquid Systems

# Single RW-EDI cell



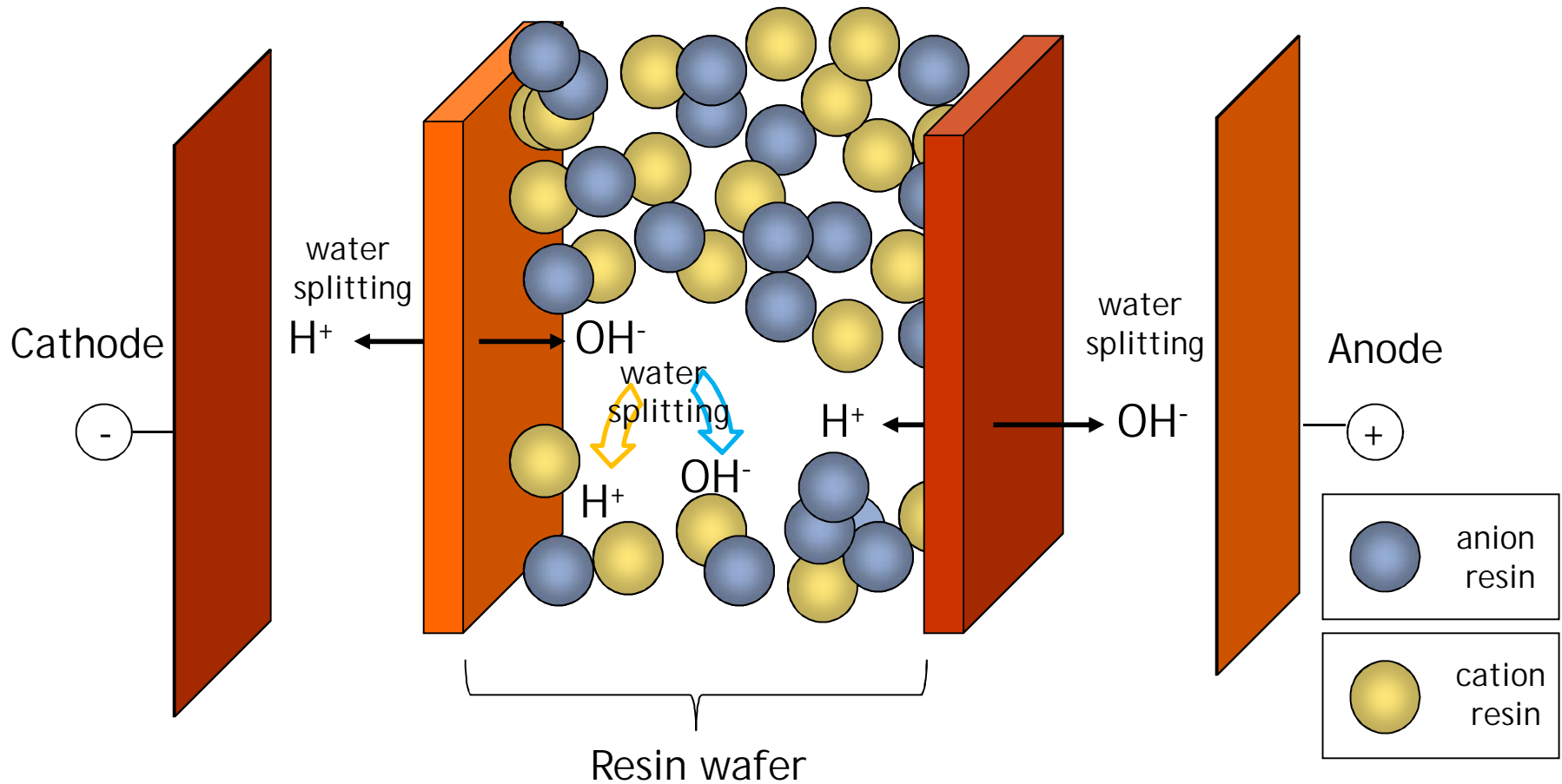
Scanning electron microscope image  
of an ion-exchange resin wafer



Resin wafer held within a gasket

# Close-up view of a single RW-EDI cell

Water splitting provides ions that continuously regenerate the ion-exchange resin and enables electrochemical solution pH control



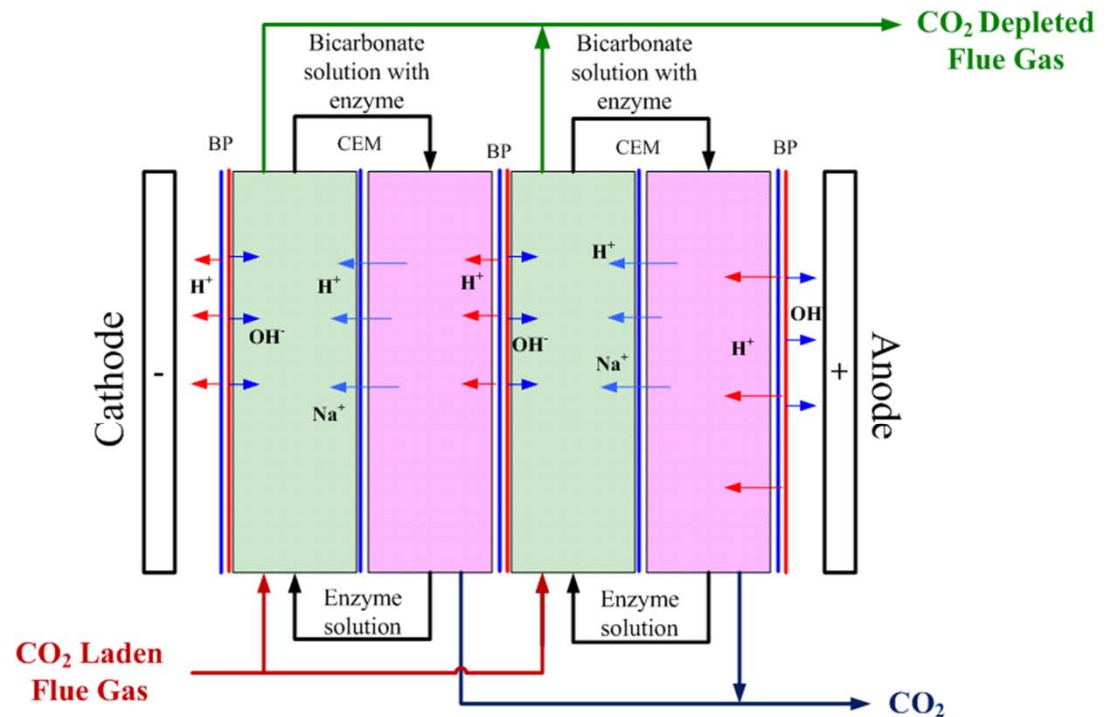
# The platform is a unique adaptation of deionization technology

The RW-EDI uses the electrochemical pH shifts to capture CO<sub>2</sub> from the flue gas and to release the CO<sub>2</sub>.

## Advantages:

- Ø Electrochemical pH control
- Ø Carbonic anhydrase enzyme drives kinetics for faster capture and release of CO<sub>2</sub>
- Ø Energy efficient CO<sub>2</sub> capture
- Ø Minimizes impact on cost of electricity

## Configuration of RW-EDI CO<sub>2</sub> Capture Device



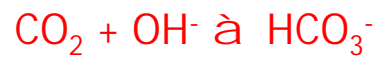
- Basic Resin Wafer for Capture
- Acidic Resin Wafer for Release
- BP: Bipolar Membrane
- CEM: Cation Exchange Membrane
- Two cell pairs are shown\*

\* A production unit would have more than 100 cell pairs

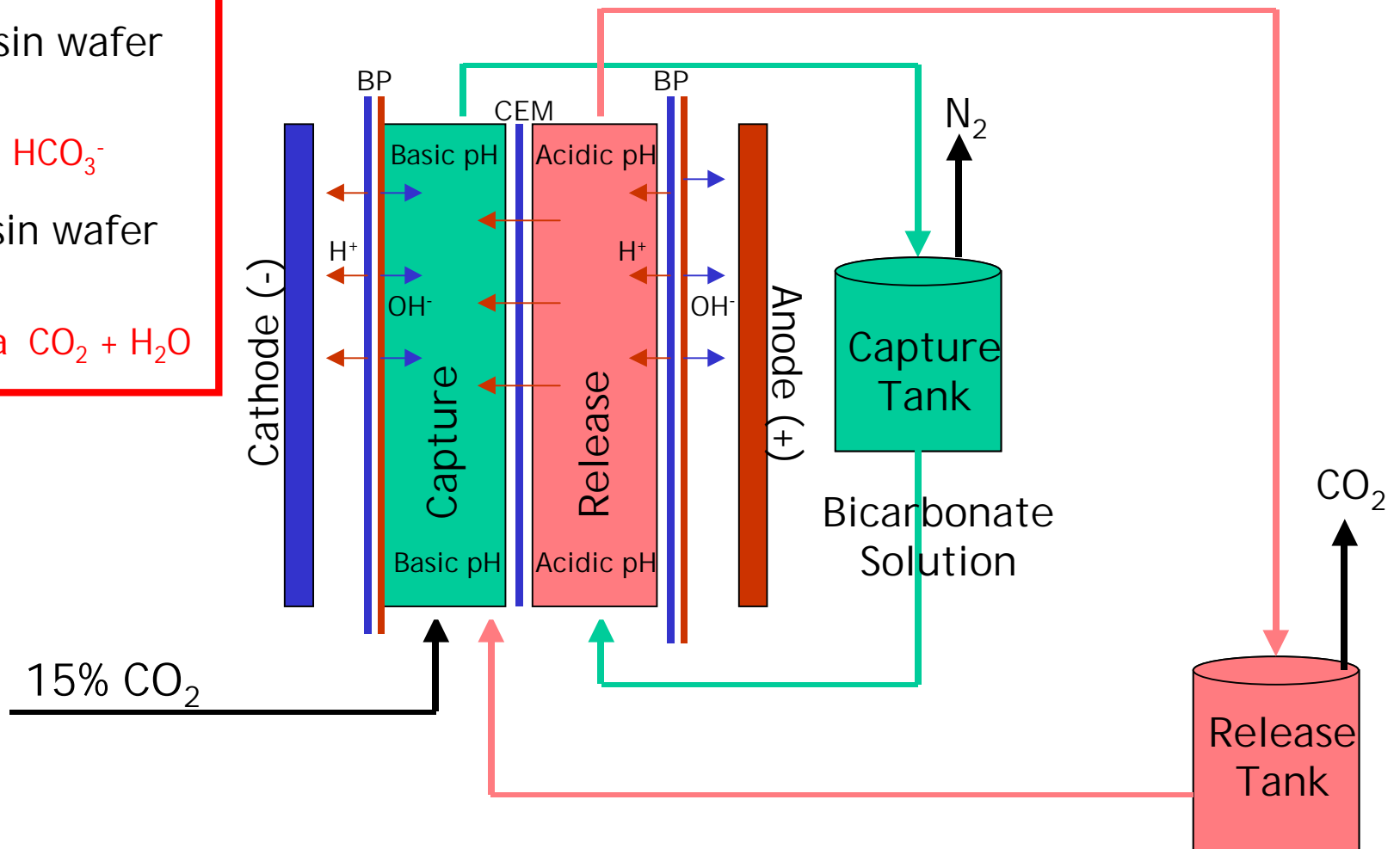


# Schematic of experimental set-up

Capture resin wafer  
(basic pH)

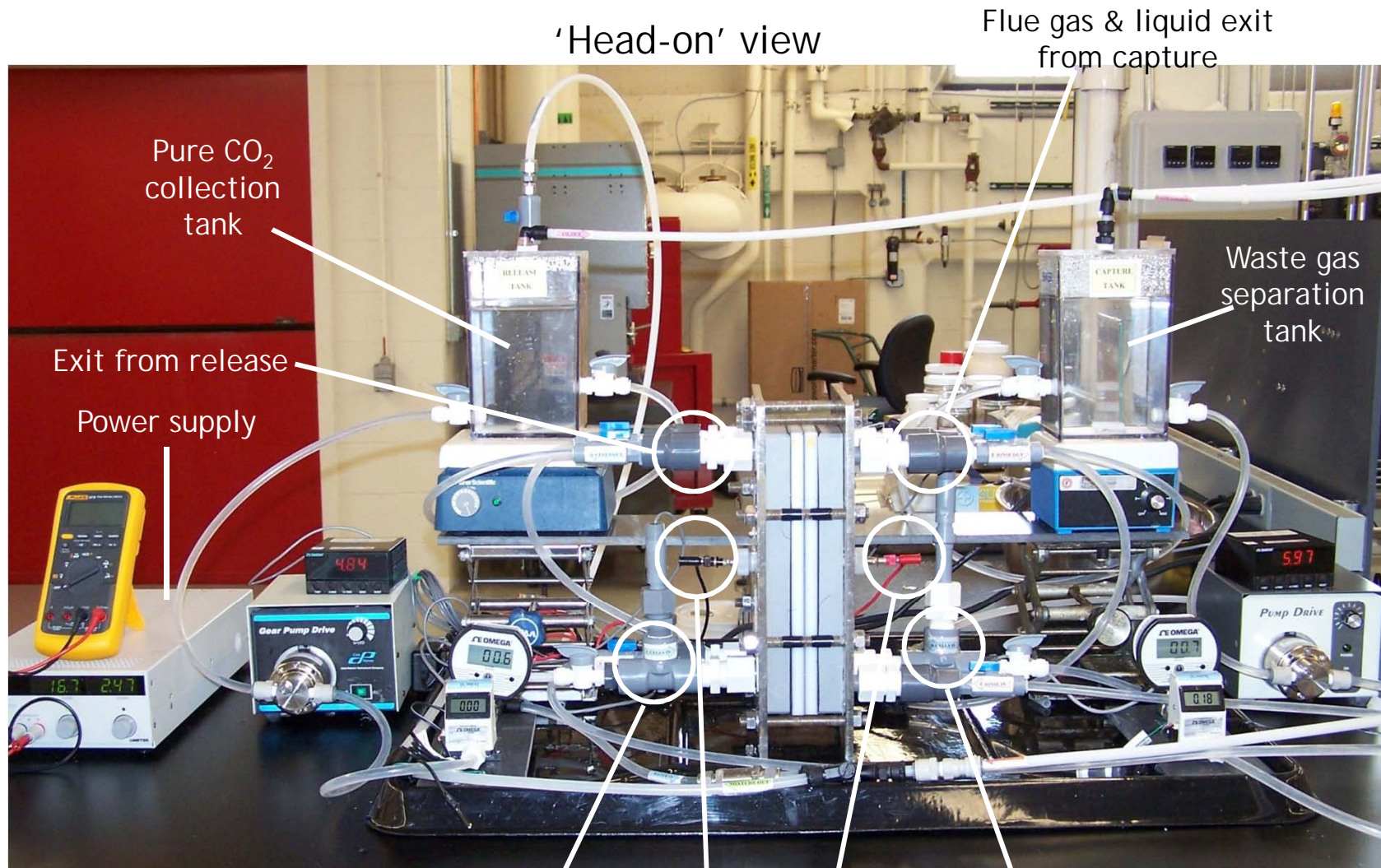


Release resin wafer  
(acidic pH)



BP: Bipolar Membrane  
CEM: Cation Exchange Membrane

# Lab-scale system with one cell pair



Flue gas & liquid into capture

Cathode

Anode

Carbon-enriched liquid into release

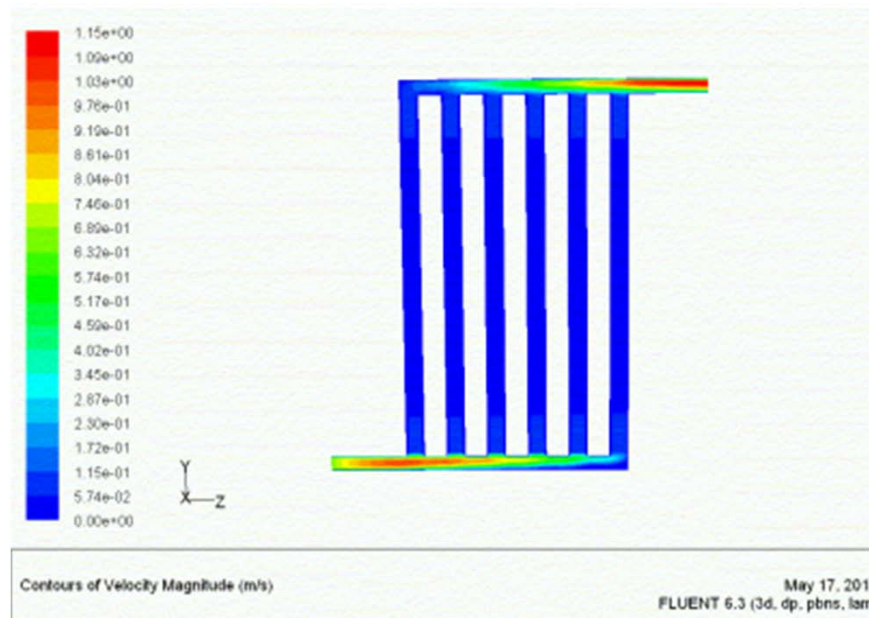
# Critical performance attributes in the research plan

- Gas-Liquid Delivery System

- Introduction of gas-liquid to the RW-EDI
- Distribution of gas and liquid among multiple cell pairs
- Mixing
- Gas-liquid separation

- Power Consumption Optimization

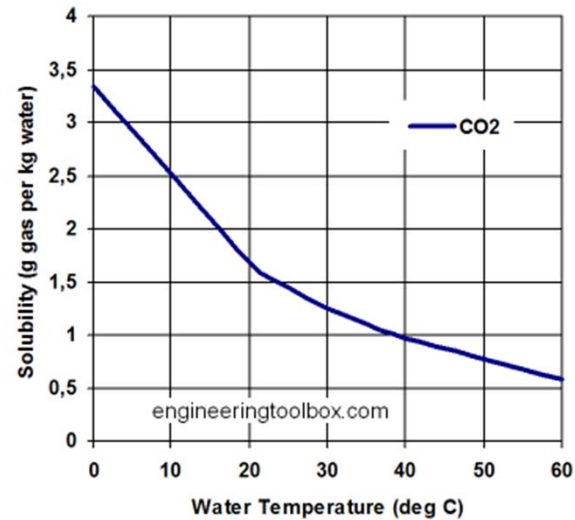
- pH control
  - Effective catalyst loading
  - Pressure drop
- Effects of Flue Gas Characteristics on Performance
  - Fine particles,  $\text{NO}_x$ ,  $\text{SO}_x$
  - Temperature



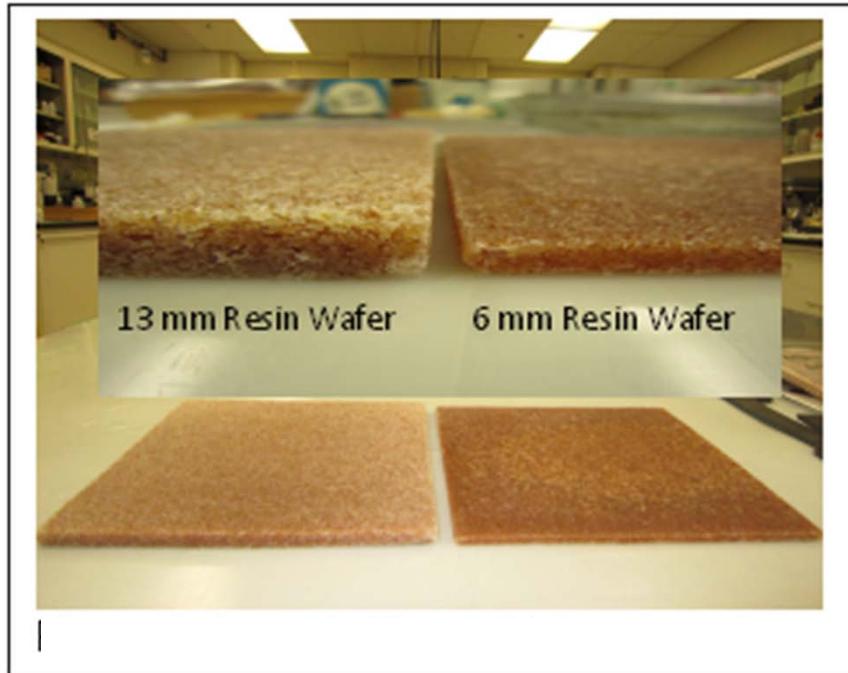
Computational fluid dynamics modeling of flow distribution in 6 parallel wafers in an RW-EDI stack.

# Proof of concept results

Capture Cell pH	Release Cell pH	% CO <sub>2</sub> Captured	% CO <sub>2</sub> Released	Comment
8.22	5.91	49	78	No Catalyst @ 25°C
7.87	5.94	44	82	No Catalyst @ 25°C



# Resin wafer fabrication



Ion-exchange resin wafers (RW) are used as the reaction chambers for CO<sub>2</sub> capture from flue gas and release as pure CO<sub>2</sub> gas. Engineering scale-up of RW fabrication was achieved and the RW properties shown below have reached the development targets.

- RW thickness and size: 6 & 13 mm in 11" x 11" and 17" x 20" sizes
- RW void space: 20% to 40% of volume
- RW ionic conductivities: 1.5 mS/cm to 4.0 mS/cm with 500 ppm NaCl
- Types of IX in RW: macroreticular resin & gel resin
- Resin particle sizes used in RW: range from 50  $\mu$ m to 400  $\mu$ m

# Efficiency improvements & macroeconomic benefits

- COE
  - Targeted in the range of 25 to 35%
- CO<sub>2</sub> purity
  - System has potential to produce >97% purity
  - Further upgrading to pipeline or utilization requirements possible
- Potential costs
  - Initially targeted at \$20 - \$40/tonne pure CO<sub>2</sub>
  - Costs likely to decrease with commercial deployment
- Potential integration with end use
  - Bicarbonate production
  - Atmospheric CO<sub>2</sub>
  - Pipeline CO<sub>2</sub>

# Acknowledgements



## Project Team

### Nalco

- Jitendra Shah
- Rebecca Stiles
- Lisa Wesoloski
- Rob Dorner
- Jerry Yuan
- Deepak Musale
- Wayne Carlson
- Cathy Doucette

### Argonne National Lab

- Seth Snyder
- Yupo Lin
- Mike Henry
- Saurav Datta
- Cindy Millard
- Michael Trachtenberg
- Dan Schabacker
- Richard Doctor

The submitted manuscript has been created by UChicago Argonne, LLC, Operator of Argonne National Laboratory ("Argonne"). Argonne, a U.S. Department of Energy Office of Science laboratory, is operated under Contract No. DE-AC02-06CH11357. The U.S. Government retains for itself, and others acting on its behalf, a paid-up nonexclusive, irrevocable worldwide license in said article to reproduce, prepare derivative works, distribute copies to the public, and perform publicly and display publicly, by or on behalf of the Government.



Nalco, logo and tagline are trademarks of Nalco Company.  
All other trademarks are property of their respective owners.

